

# Greg Denbeaux

## List of Publications by Year in descending order

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Version: 2024-02-01

21  
papers

263  
citations

1040056

9  
h-index

940533

16  
g-index

21  
all docs

21  
docs citations

21  
times ranked

178  
citing authors

#	ARTICLE	IF	CITATIONS
1	Secondary Electrons in EUV Lithography. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2013, 26, 625-634.	0.3	53
2	Resolution, Line-Edge Roughness, Sensitivity Tradeoff, and Quantum Yield of High Photo Acid Generator Resists for Extreme Ultraviolet Lithography. Japanese Journal of Applied Physics, 2011, 50, 036504.	1.5	31
3	Resolution, Line-Edge Roughness, Sensitivity Tradeoff, and Quantum Yield of High Photo Acid Generator Resists for Extreme Ultraviolet Lithography. Japanese Journal of Applied Physics, 2011, 50, 036504.	1.5	25
4	Magnetization reversal study of CoCrPt alloy thin films on a nanogranular-length scale using magnetic transmission soft x-ray microscopy. Applied Physics Letters, 2003, 83, 4589-4591.	3.3	21
5	What We Don't Know About EUV Exposure Mechanisms. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2017, 30, 113-120.	0.3	19
6	Acid Generation Efficiency of EUV PAGs via Low Energy Electron Exposure. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2016, 29, 453-458.	0.3	18
7	RLS tradeoff vs. quantum yield of high PAG EUV resists. , 2009, , .		13
8	Electron Penetration Depths in EUV Photoresists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2014, 27, 611-615.	0.3	13
9	Cross sections of photoacid generators at low electron energies. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2015, 33, 06FH01.	1.2	11
10	EUV Mechanistic Studies of Antimony Resists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2017, 30, 121-131.	0.3	11
11	Mechanisms of EUV exposure: electrons and holes. , 2017, , .		8
12	Reactivity of metal-oxalate EUV resists as a function of the central metal. Proceedings of SPIE, 2017, , .	0.8	8
13	Studying thickness loss in extreme ultraviolet resists due to electron beam exposure using experiment and modeling. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2015, 14, 043502.	0.9	7
14	Spectromicroscopy at the XM-1. AIP Conference Proceedings, 2000, , .	0.4	6
15	Antimony photoresists for EUV lithography: mechanistic studies. Proceedings of SPIE, 2017, , .	0.8	6
16	Analytical techniques for mechanistic characterization of EUV photoresists. Proceedings of SPIE, 2017, , .	0.8	6
17	Cross sections of EUV PAGs: influence of concentration, electron energy, and structure. , 2016, , .		3
18	Isotopic Labeling Studies of EUV Photoresists Containing Antimony. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 233-242.	0.3	2

#	ARTICLE	IF	CITATIONS
19	Energy deposition and charging in EUV lithography: Monte Carlo studies. , 2016, , .		1
20	Imaging magnetic microstructures of with soft X-ray microscopies. Transactions of the Magnetics Society of Japan, 2002, 2, 234-237.	0.5	1
21	EUV Photochemistry of $\hat{\pm}$ -Substituted Antimony Carboxylate Complexes. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2021, 34, 81-86.	0.3	0